	Application No.	Applicant(s)	
Notice of Allowability	10/807,000	KIM ET AL.	
	Examiner	Art Unit	
	Thinh T. Mauren	2818	
•	Thinh T. Nguyen	2010	
The MAILING DATE of this communication appeall claims being allowable, PROSECUTION ON THE MERITS IS therewith (or previously mailed), a Notice of Allowance (PTOL-85) NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT RIP of the Office or upon petition by the applicant. See 37 CFR 1.313	(OR REMAINS) CLOSED in this apport or other appropriate communication IGHTS. This application is subject to	plication. If not included n will be mailed in due course. THIS	3 Itive
1. This communication is responsive to 10/3/2005.	·		
2. ☑ The allowed claim(s) is/are <u>1-22 and 36-41</u> .			
 3.			
2. Certified copies of the priority documents have	e been received in Application No.	•	
3. Copies of the certified copies of the priority do		·	!
International Bureau (PCT Rule 17.2(a)).			
* Certified copies not received:			
Applicant has THREE MONTHS FROM THE "MAILING DATE" noted below. Failure to timely comply will result in ABANDONN THIS THREE-MONTH PERIOD IS NOT EXTENDABLE.	of this communication to file a reply IENT of this application.	complying with the requirements	
 A SUBSTITUTE OATH OR DECLARATION must be subm INFORMAL PATENT APPLICATION (PTO-152) which give 	itted. Note the attached EXAMINER es reason(s) why the oath or declara	'S AMENDMENT or NOTICE OF ition is deficient.	
5. CORRECTED DRAWINGS (as "replacement sheets") mus	st be submitted.		
(a) including changes required by the Notice of Draftspers	son's Patent Drawing Review (PTO-	948) attached	
1) hereto or 2) to Paper No./Mail Date			
(b) including changes required by the attached Examiner's Paper No./Mail Date	s Amendment / Comment or in the C	Office action of	
Identifying indicia such as the application number (see 37 CFR 1 each sheet. Replacement sheet(s) should be labeled as such in t	.84(c)) should be written on the drawing the header according to 37 CFR 1.121(ngs in the front (not the back) of d).	
 DEPOSIT OF and/or INFORMATION about the depo attached Examiner's comment regarding REQUIREMENT 	sit of BIOLOGICAL MATERIAL r FOR THE DEPOSIT OF BIOLOGIC	nust be submitted. Note the AL MATERIAL.	
•			
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Attachment(s) 1. ☐ Notice of References Cited (PTO-892)	5 ☐ Notice of Informal F	Patent Application (PTO-152)	
2. ☐ Notice of Draftperson's Patent Drawing Review (PTO-948)	6. ☐ Interview Summary	···	
3. ☑ Information Disclosure Statements (PTO-1449 or PTO/SB/0	Paper No./Mail Da 08), 7. ⊠ Examiner's Amendr		
``Paper No./Mail Date	<i>,</i> , –		
 Examiner's Comment Regarding Requirement for Deposit of Biological Material 		ent of Reasons for Allowance	
	9. 🗌 Other	Mr J Ny	
		Nigen Van Ngo	

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DETAILED ACTION

Examiner's Amendment.

1. An examiner's amendment to the record appears below. Should the changes and/or additions be unacceptable to applicant, an amendment may be filed as provided by 37 CFR 1.312. To ensure consideration of such an amendment, it MUST be submitted no later than the payment of the issue fee.

Change the title to:

-- INTEGRATED CIRCUIT DEVICES WITH METAL-INSULATOR-METAL CAPACITORS --

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Reason for allowance

2. Claims 1-22,36-41 are allowed. The following is an examiner's statement of reason for allowance:

I/ Group I: Claims 1-12,36-37,40

Claims 1-12,36-37,40 are allowed because None of the references of record teaches or suggests the claimed INTEGRATED CIRCUIT DEVICES WITH METAL-INSULATOR-METAL CAPACITORS DEVICE having the limitations:

-- "a dielectric layer on the substrate. a conductive contact plug extending through an opening in the dielectric layer to contact the substrate and including a widened pad portion extending onto the dielectric layer adjacent the opening; an ohmic pattern on the pad portion of the plug; a barrier pattern on the ohmic pattern; a concave first capacitor electrode disposed on the barrier pattern and defining a cavity opening away from the substrate, a capacitor dielectric layer conforming to a surface of the first capacitor electrode; and a second capacitor electrode disposed on the capacitor dielectric layer opposite the first capacitor electrode. "--

in claim 1.

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II/ Group II: Claims 13-22,38-39,41

Claims 13-22,38-39,41 are allowed because None of the references of record teaches or suggests the claimed INTEGRATED CIRCUIT DEVICES WITH METAL-INSULATOR-METAL CAPACITORS DEVICE having the limitations:

"a dielectric layer on the substrate-, a conductive contact plug extending through an opening in the dielectric layer to contact the substrate and including a widened pad portion extending onto the dielectric layer adjacent the opening; stacked ohmic and barrier patterns disposed on the pad portion of the plug and having sidewalls substantially coplanar with a sidewall of the pad portion; a first capacitor electrode disposed on the barrier pattern; a capacitor dielectric layer on the first capacitor electrode; and a second capacitor electrode on the capacitor dielectric layer opposite the first capacitor electrode. "--

in claim 13.

Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance".

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Conclusion

3. Any inquiry concerning this communication or earlier communications from the examiner should be directed to Thinh T Nguyen whose telephone number is 571-272-1790. The examiner can normally be reached on Monday-Friday 9:00am-6:00pm.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, David Nelms can be reached at 571-272-1787. The fax phone numbers for the organization where this application or proceeding is assigned are (703) 872-9306 for regular communications and (703) 872-9319 for After Final communications.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval [PAIR] system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

Thinh T Nguyen

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Ngen Van Ngo Primary Examiner

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